

U.S.S.N. 10/816,089

REMARKS

Claim 1 is amended to correct typographical errors.

The election of Species requirement imposed by the Examiner is respectfully traversed for the following reasons. Both Figures 1F and 2E show a gate structure having a double-layered sidewall spacer formed of oxide and nitride. Furthermore, both the structures shown in Figure 1F and 2E show source-drain extension regions comprising the semiconductor substrate **extend beyond a maximum width of the spacers**. The Applicants therefore respectfully submit that the two Figures 1F and 2E do not show inventions of two different species.

In the event that the present invention is not in a condition for allowance for any other reasons, the Examiner is respectfully invited to telephone the Applicants' representative at his Bloomfield Hills, Michigan office at (248) 540-4040 such that necessary action may be taken to place the application in a condition for allowance.

Respectfully submitted.

TUNG & ASSOCIATES

Randy W. Tung
Reg. No. 31,311
Telephone: (248) 540-4040